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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/080,848	02/22/2002	Hiroto Ohtake	KRM-00101	9662
26339	7590 10/07/2004		EXAMINER	
PATENT GROUP CHOATE, HALL & STEWART EXCHANGE PLACE, 53 STATE STREET			DEO, DUY VU NGUYEN	
			ART UNIT	PAPER NUMBER
BOSTON, N	AA 02109		1765	
			DATE MAILED: 10/07/2004	4

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
	10/080,848	OHTAKE ET AL.				
Office Action Summary	Examiner	Art Unit				
	DuyVu n Deo	1765				
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet w	ith the correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a rep If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailir earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a soly within the statutory minimum of thi will apply and will expire SIX (6) MO e, cause the application to become A	reply be timely filed ty (30) days will be considered timely. ITHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 14 J	luly 2004.					
<u> </u>						
3) Since this application is in condition for allowa	· ·					
closed in accordance with the practice under	Ex parte Quayle, 1935 C.I	D. 11, 453 O.G. 213.				
Disposition of Claims						
4) □ Claim(s) 20-28 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) □ Claim(s) is/are allowed. 6) □ Claim(s) 20-28 is/are rejected. 7) □ Claim(s) is/are objected to. 8) □ Claim(s) are subject to restriction and/or	awn from consideration.					
Application Papers	·					
9)☐ The specification is objected to by the Examina 10)☐ The drawing(s) filed on 14 July 2004 is/are: a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11)☐ The oath or declaration is objected to by the E)⊠ accepted or b)⊡ obje e drawing(s) be held in abeya ction is required if the drawing	nce. See 37 CFR 1.85(a). I(s) is objected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documen 2. Certified copies of the priority documen 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	its have been received. Its have been received in a prity documents have been au (PCT Rule 17.2(a)).	Application No received in this National Stage				
Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948)		Summary (PTO-413) s)/Mail Date				
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date <u>7/23/04</u>. 		nformal Patent Application (PTO-152)				

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DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- (e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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3. Claims 20-27 are rejected under 35 U.S.C. 102(e) as being anticipated by Farrar (US 6,395,632).

Farrar describes a semiconductor device comprising (claims 20 and 23): a substrate, an insulating layer 57a, formed on the substrate, made of material including SILK (claimed organic film having low dielectric constant and including no silicon) (col. 4,line 25, line 46-51) is formed between insulating films 55a and 57, made from material including BCB (claimed silicon included organic film) (col. 4, line 20-25; col. 7, line 1-15).

Referring to claims 21 and 24, a conductive is selectively buried into opening portion or trench of the stack films of the insulating films 55 and 57 (fig. 14).

Referring to claims 22, 25, 26, and 27, the BCB film would read on claimed silicon included organic film formed by a polymer of divinyl-siloxane-benzocyclobutene or siloxane-polymide and have the same chemical formula as that of claimed 25 (please all see cited Maex et al. cited below).

4. Claim 28 is rejected under 35 U.S.C. 102(e) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Farrar.

Referring to claim 28, the layer 55a (claimed hardmask) for used in etching the layer 57a (figure 21) and layer 57 (claimed etching stopping layer) would inherently capable of for use in etching of the organic film since their material, BCB, read on claimed silicon included organic layer as described above. In the alternative, it would be obvious for one skill in the art to use it for etching the organic film with a reasonable expectation success.

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5. Maex et al. (US 2003/0162407) is cited to show prior art (paragraph [0038]).

Priority

6. Acknowledgment is made of applicant's claim for foreign priority based on an application filed in Japan on 2/22/01. It is noted, however, that applicant has not filed a certified copy of the Japanese application as required by 35 U.S.C. 119(b).

Response to Arguments

7. Applicant's arguments with respect to claims 20-28 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

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9. Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n Deo whose telephone number is 571-272-1462. The examiner can normally be reached on 6:00-3:30; with alternate Friday off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571-272-1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DVD 10/05/04 Q, Q